

Appl. No. 10/507,100
Amdt. dated June 13, 2006
Reply to Office action of March 13, 2006
Atty. Docket No. AP928USN

Amendments to the Specification:

Please replace the paragraph beginning at page 3, line 15 with the following amended paragraph:

-- According to the present invention, a photosensitive material comprises ~~at least one organic species in a host matrix formed by an inorganic network and an organic-inorganic network interpenetrating each other, the host matrix containing at least one organic species comprising a material having a refractive index which changes upon exposure to actinic radiation wherein the host matrix comprises a material formed by interpenetrating networks and inorganic and organically modified phases.~~ --

Please replace the paragraph beginning at page 4, line 1 with the following amended paragraph:

— According to a second aspect of the invention, there is provided a process of making a photosensitive material comprising the steps of forming a host matrix comprising an inorganic network and an organic-inorganic network interpenetrating each other, the host matrix containing at least one organic species having a refractive index that changes on exposure to actinic radiation; ~~wherein the host matrix is formed by interpenetrating networks of inorganic and organically modified phases.~~ —